

## Benchtop Plasma System

The PE-200 is a complete industrial grade plasma treatment solution – capable of plasma cleaning, plasma etching, reactive ion etching, and more.

This model is available in one of three possible configurations:

- 1) Plasma Cleaning/Plasma Etching
- 2) Reactive Ion Etching (RIE)
- 3) Convertible Configuration – Includes both isotropic and anisotropic plasma processing in a single system. Removable tray configuration.



### STANDARD FEATURES

Electrode Configuration	Three Stacked Horizontal (13"Wx16"D + 3" Clearance)
Generator	300W 13.56MHz Continuously Variable Power Supply with Automatic Matching Network
Gas Control	One 0-200cc Mass Flow Controller
Control System	Laptop Equipped with Plasma Etch Inc.'s Control Software for Fully Automatic System Operation
Vacuum Gauge	1-2000 mT
Vacuum Pump	29CFM 2-Stage Direct Drive Oil Pump (Oxygen Service – Krytox Charged)
Chamber	17" x 17" x 14"; 6061-T6 Aluminum
Unit Dimensions	18" x 19" x 24"
Unit Weight	350lbs; 500lbs with Vacuum Pump

### FACILITY REQUIREMENTS

Electrical	120V/208VAC (Five Wire, Three Phase) or 208VAC (Four Wire, Three Phase)
Compressed Air Service	80-100PSI, 0.5CFM
Regulated Process Gases	15PSI, 2-Stage Regulator

### OPTIONAL FEATURES

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| <ul style="list-style-type: none"><li>• Custom Vacuum Chamber or Electrode Size</li><li>• Reactive Ion Electrodes</li><li>• MHz Power Supplies with Automatic Matching Network</li><li>• PC-Based Control System</li><li>• Electrostatic Shielding</li><li>• Temperature Control System</li><li>• Dry Vacuum Pump</li><li>• Chiller System for Dry Vacuum Pump</li><li>• Chamber and Vacuum Pump Purge Systems</li></ul> | <ul style="list-style-type: none"><li>• Vacuum Pump Oil Mist Eliminator</li><li>• Vacuum Pump Oil Filtration</li><li>• Automatic Vacuum Control</li><li>• Additional Digital Mass Flow Controllers</li><li>• Software Configurable Gas Steering Matrix 2x5</li><li>• Low Gas-Source Alarm</li><li>• Light Tower</li><li>• Fume Scrubber</li></ul> |
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